

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-15 (Canceled)

Claim 16 (Original): An exposure apparatus, comprising:

an exposure apparatus main body that transfers a predetermined pattern onto a substrate;

an exposure chamber that houses at least a part of said exposure apparatus main body, and in which environmental conditions are kept substantially constant;

a machine chamber connected to said exposure chamber via a supply path and via an exhaust path;

an air conditioner arranged in said machine chamber that includes a cooler to cool gas for air conditioning circulating within the machine chamber and that performs air conditioning inside said exposure chamber; and

a controller that controls the surface temperature of said cooler so that condensation does not occur.

Claim 17 (Original): The exposure apparatus according to claim 16, wherein

said air conditioner further includes a heater that is arranged in said machine chamber and that heats said cooled gas.

Claim 18 (Original): The exposure apparatus according to claim 16, further comprising:

a drain pan arranged below said cooler in a direction of gravity.

Claim 19 (Original): The exposure apparatus according to claim 18, wherein said drain pan is a drain pan that is not connected to a pipe system.

Claim 20 (Original): The exposure apparatus according to claim 16, wherein said exposure apparatus main body includes a substrate stage that holds said substrate and an interferometer that measures a position of said substrate stage, and said exposure apparatus further comprising: another air conditioner that performs air conditioning of a part of the space inside said exposure chamber, where said substrate stage and said interferometer are arranged, independently of said air conditioner.

Claim 21 (Original): The exposure apparatus according to claim 20, wherein said another air conditioner shares a part of said air conditioner.

Claim 22 (Original): The exposure apparatus according to claim 16, wherein a surface of said substrate is coated with a chemically amplified resist as a photosensitive agent.

Claim 23 (Original): A device manufacturing method including a lithography process, wherein exposure is performed in said lithography process by using the exposure apparatus according to claim 16.

Claims 24-35 (Canceled)

Claim 36 (Original): An environmental control method of an exposure apparatus that supplies gas at least the temperature of which is controlled into an exposure chamber that houses at least a part of an exposure apparatus main body such that environmental conditions are kept substantially constant inside said exposure chamber, said exposure apparatus main body transferring a predetermined pattern onto a substrate, wherein

said gas is made to pass through a cooler before supplying said gas into said exposure chamber and the surface temperature of said cooler is set at such a temperature that condensation does not occur.

Claim 37 (Original): An exposure apparatus, comprising:

an exposure apparatus main body that transfers a predetermined pattern onto a substrate;

a substrate transportation system that transports said substrate to said exposure apparatus main body;

a first chamber that houses at least a part of said exposure apparatus main body and in which environmental conditions are kept substantially constant;

a first return duct an end of which is connected to said first chamber and through which gas exhausted from said first chamber passes;

a second chamber that houses at least a part of said substrate transportation system and in which environmental conditions are kept substantially constant;

a second return duct an end of which is connected to said second chamber and through which gas exhausted from said second chamber passes; and

a first chemical substance removing filter that is connected to another end than said end of said first return duct and to another end than said end of said second return duct and that removes chemical impurities in both of gas exhausted from said first chamber and gas exhausted from said second chamber.

Claim 38 (Original): The exposure apparatus according to claim 37, further comprising:

a mask transportation system that transports a mask on which said predetermined pattern is formed.

Claim 39 (Original): The exposure apparatus according to claim 38, wherein said mask transportation system includes a storing section that stores a plurality of masks.

Claim 40 (Original): The exposure apparatus according to claim 38, further comprising:

a third chamber that houses at least a part of said mask transportation system and in which environmental conditions are kept substantially constant; and

a third return duct an end of which is connected to said third chamber and through which gas exhausted from said third chamber passes, and wherein

another end than said end of said third return duct is connected to said chemical substance removing filter together with said another end of said first return duct and said another end of said second return duct.

Claim 41 (Original): The exposure apparatus according to claim 37, further comprising:

a machine chamber in which a cooler, a heater and a blower that blows temperature-adjusted gas to said first chamber are arranged, and wherein

said first chemical substance removing filter is arranged inside said machine chamber and is connected to both of said another end of said first return duct and said another end of said second return duct via an opening made in part of said machine chamber.

Claim 42 (Original): The exposure apparatus according to claim 41, further comprising:

a second chemical substance removing filter that is arranged in part of a supply path for supplying temperature-adjusted gas from said machine chamber at least to said first chamber and removes chemical impurities in said temperature-adjusted gas.

Claim 43 (Original): The exposure apparatus according to claim 42, wherein said machine chamber and said first chamber are connected to each other to be separable, and

wherein said second chemical substance removing filter is arranged in the vicinity of the connection between said machine chamber and said first chamber.

Claim 44 (Previously Presented): An environmental controller suitable for environmental control inside an environmental control chamber in which an exposure apparatus that transfers a predetermined pattern onto a substrate is arranged, said environmental controller comprising:

a blower that blows air into said environmental control chamber;

a cooler that is arranged upstream of said blower and cools down the air blown into said environmental control chamber by said blower;

a sensor that is arranged on said cooler and detects the temperature of a surface of said cooler; and

a controller that controls said cooler in accordance with a detection result of the surface temperature of said cooler supplied from said sensor so that condensation does not occur on the surface of the cooler.

Claim 45 (Previously Presented): The environmental controller according to claim 44, wherein

said controller controls said cooler in accordance with a detection result of said sensor so that condensation does not occur on the surface of said cooler in the humidity and pressure of air passing through said cooler.

Claim 46 (Previously Presented): The environmental controller according to claim 45, further comprising:

a drain pan that is arranged below said cooler and has no pipe system connected to the outside.

Claim 47 (Previously Presented): The environmental controller according to claim 46, wherein

said controller controls said cooler in accordance with a detection result of said sensor to maintain said surface temperature between 5 °C and 15 °C so that condensation does not occur on the surface of said cooler.